# **Guojin Chen**

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### **Education**

Ph.D. in Computer Science, Chinese University of Hong Kong
Supervisor: Prof. Bei Yu

M.S. in Computer Science, Chinese University of Hong Kong

B.S. in Computer Science, Huazhong University of Science and Technology

2021 – Present
2019 – 2020
2015 – 2019

### **Experiences**

DeepMind Google DeepMind, Ph.D. Student Researcher

2024.07 - 2024.10 Mountain view, CA

NVIDIA, Research Scientist Intern (Mentor & Manager. Haoyu Yang & Mark Ren)

2024.04 - 2024.07

**TEXAS** University of Texas at Austin, Visiting Scholar

2023.08 - 2024.4

(Supervisor : Prof. David Z. Pan)

2023.08 – 2024.4 Austin, TX

Austin, TX

Tencent Tencent, Intern

2018 Shenzhen, China

# **Research Interests**

#### Research Overview

To learn more about my research, click this link for a detailed document with rich text and images.

- O Scaling deep learning: large language models, LLM on EDA, large-scale layout representation learning.
- Design for manufacturing: computational lithography, mask optimization, OPC, SMO.
- Deep learning in VLSI design: physics-informed networks for EDA problems
- Optimization: bi-level & multi-level optimization, GPU acceleration, level-set optimization.

#### **Publications** [Google Scholar; 229+ citations, h-index: 8+]

Representative publications that I am a primary author on are highlighted.

#### Conference papers.....

- [C17] PACE: Pacing Operator Learning to Accurate Optical Field Simulation for Complicated Photonic Devices Hanqing Zhu, Wenyan Cong, **Guojin Chen**, Shupeng Ning, Ray Chen, Jiaqi Gu, and David Z. Pan (**NeurIPS 2024**) The Thirty-eighth Annual Conference on Neural Information Processing Systems
- [C16] Differentiable Edge-based OPC

  Guojin Chen, Haoyu Yang, Haoxing Ren, Bei Yu, and David Z. Pan

  (ICCAD 2024) Proceedings of the 43rd International Conference on Computer-Aided Design
- [C15] Efficient Bilevel Source Mask Optimization

  Guojin Chen, Hongquan He, Peng Xu, Hao Geng, and Bei Yu

  (DAC 2024) ACM/IEEE Design Automation Conference
- [C14] Fracturing-aware Curvilinear ILT via Circular E-beam Mask Writer Xinyun Zhang, Su Zheng, Guojin Chen, Binwu Zhu, Hong Xu, and Bei Yu (DAC 2024) ACM/IEEE Design Automation Conference
- [C13] Performance-driven Analog Routing via Heterogeneous 3DGNN and Potential Relaxation Peng Xu, Guojin Chen, Keren Zhu, Tinghuan Chen, Tsung-Yi Ho, and Bei Yu (DAC 2024) ACM/IEEE Design Automation Conference
- [C12] Open-Source Differentiable Lithography Imaging Framework Guojin Chen, Hao Geng, Bei Yu, and David Z. Pan (SPIE 2024) SPIE Advanced Lithography + Patterning

- [C11] AlphaSyn: Logic Synthesis Optimization with Efficient Monte Carlo Tree Search Zehua Pei, Fangzhou Liu, Zhuolun He, **Guojin Chen**, Haisheng Zheng, Keren Zhu, and Bei Yu (**ICCAD 2023**) Proceedings of the 42th International Conference on Computer-Aided Design
- [C10] Physics-Informed Optical Kernel Regression Using Complex-valued Neural Fields

  Guojin Chen, Zehua Pei, Haoyu Yang, Yuzhe Ma, Bei Yu, and Martin Wong

  (DAC 2023) ACM/IEEE Design Automation Conference (Best score in DFM track.)
- [C9] DiffPattern: Layout Pattern Generation via Discrete Diffusion Zixiao Wang, Yunheng Shen, Wenqian Zhao, Yang Bai, Guojin Chen, Farzan Farnia, and Bei Yu (DAC 2023) ACM/IEEE Design Automation Conference
- [C8] GPU-accelerated Matrix Cover Algorithm for Multiple Patterning Layout Decomposition Guojin Chen, Haoyu Yang, and Bei Yu (SPIE 2023) DTCO and Computational Patterning II
- [C7] Efficient Point Cloud Analysis Using Hilbert Curve.
  Wanli Chen, Xinge Zhu, Guojin Chen, and Bei Yu
  (ECCV 2022) European Conference on Computer Vision
- [C6] AdaOPC: A Self-Adaptive Mask Optimization Framework For Real Design Patterns Wenqian Zhao, Xufeng Yao, Ziyang Yu, **Guojin Chen**, Yuzhe Ma, Bei Yu, and Martin Wong (**ICCAD 2022**) *Proceedings of the 41th International Conference on Computer-Aided Design*
- [C5] LayouTransformer: Generating Layout Patterns with Transformer via Sequential Pattern Modeling Liangjian Wen, Yi Zhu, Lei Ye, **Guojin Chen**, Bei Yu, Jianzhuang Liu, and Chunjing Xu (ICCAD 2022) Proceedings of the 41th International Conference on Computer-Aided Design
- [C4] DevelSet: Deep Neural Level Set for Instant Mask optimization

  Guojin Chen, Ziyang Yu, Hongduo Liu, Yuzhe Ma, and Bei Yu

  (ICCAD 2021) Proceedings of the 40th International Conference on Computer-Aided Design
- [C3] Learning Point Clouds in EDA.
  Wei Li, Guojin Chen, Haoyu Yang, Ran Chen, and Bei Yu
  (ISPD 2021) ACM International Symposium on Physical Design
- [C2] DAMO: Deep Agile Mask Optimization for Full Chip Scale

  Guojin Chen, Wanli Chen, Yuzhe Ma, Haoyu Yang, and Bei Yu

  (ICCAD 2020) Proceedings of the 39th International Conference on Computer-Aided Design
- [C1] A GPU-enabled Level Set Method for Mask Optimization Ziyang Yu, Guojin Chen, Yuzhe Ma, and Bei Yu (DATE 2020) IEEE/ACM Proceedings Design, Automation and Test in Europe

### Journal papers..

- [J6] DeepOTF: Learning Equations-constrained Prediction for Electromagnetic Behavior Peng Xu, Siyuan Xu, Tinghuan Chen, Guojin Chen, Tsung-Yi Ho, and Bei Yu (TODAES 2024) ACM Trans. Des. Autom. Electron. Syst.
- [J5] Ultra-Fast Source Mask Optimization via Conditional Discrete Diffusion

  Guojin Chen, Zixiao Wang, Bei Yu, David Z. Pan, and Martin D.F. Wong

  (TCAD 2024) IEEE Transactions on Computer-Aided Design of Integrated Circuits and Systems
  - [J4] L2O-ILT: Learning to Optimize Inverse Lithography Techniques
    Binwu Zhu, Su Zheng, Ziyang Yu, **Guojin Chen**, Yuzhe Ma, Fan Yang, Bei Yu, and Martin Wong
    (**TCAD 2023**) *IEEE Transactions on Computer-Aided Design of Integrated Circuits and Systems*
  - [J3] A GPU-Enabled Level-Set Method for Mask Optimization
    Ziyang Yu, Guojin Chen, Yuzhe Ma, and Bei Yu
    (TCAD 2023) IEEE Transactions on Computer-Aided Design of Integrated Circuits and Systems
- [J2] DevelSet: Deep Neural Level Set for Instant Mask optimization

  Guojin Chen, Ziyang Yu, Hongduo Liu, Yuzhe Ma, and Bei Yu

  (TCAD 2023) IEEE Transactions on Computer-Aided Design of Integrated Circuits and Systems

[J1] DAMO: Deep Agile Mask Optimization for Full-Chip Scale **Guojin Chen**, Wanli Chen, Qi Sun, Yuzhe Ma, Haoyu Yang, and Bei Yu

(**TCAD 2022**) IEEE Transactions on Computer-Aided Design of Integrated Circuits and Systems

# Preprints....

[P1] LLM-Enhanced Bayesian Optimization for Efficient Analog Layout Constraint Generation **Guojin Chen**, Keren Zhu, Seunggeun Kim, Hanqing Zhu, Yao Lai, Bei Yu, and David Z Pan (arXiv 2024) arXiv preprint arXiv:2406.05250

# **Open Source Repositories**

1. TorchOPC/TorchLitho ★161 Differentiable computational lithography with PyTorch	2024
2. dekura/LLANA ★10 LLM-Enhanced Bayesian Optimization for Efficient Analog Constraint Genera-	2024
tion	
3. OpenOPC/OpenILT ★113 Open-source inverse lithography technology (ILT) framework	2023
4. ai4eda/awesome-Al4EDA ★118 A curated paper list of existing AI for EDA studies.	2023

## **Awards**

Ph.D. Studentship	2021 – 2025
By Chinese University of Hong Kong, 2021-2025 Outstanding Graduate	2019
By Huazhong University of Science and Technology	

# **Professional Activities**

Paper Review / External Review	
Neural Information Processing Systems (NeurIPS)	2023-2024
Design Automation Conference (DAC)	2021-2024
AAAI Conference on Artificial Intelligence (AAAI)	2022-2025
IEEE Transactions on Computer-Aided Design of Integrated Circuits and Systems (TCAD)	2022-2024